	Hits	Search Text	DBs
37	10	(temperature or heat or anneal\$4)) and (RIE near16	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
38	1	((spin near9 glass) near16 (method or deposit\$4 or form\$4) near36 ((photoresist or resist	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
39	I()	baking near12 evaporating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
40	31	baking near12 evaporat\$4 near12	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB